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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:  
Cohen, et al.

Serial No.: 09/206,027

Filed: December 4, 1998

For: Plasma Preclean With Argon,  
Helium, and Hydrogen Gases

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Group Art Unit: 1765

Examiner: L. Vinh

Assistant Commissioner for Patents  
Washington, D.C. 20231

Dear Sir:

CERTIFICATE OF MAILING 37 CFR 1.8	
I hereby certify that this correspondence is being deposited on May 15, 2001 with the United States Postal Service as First Class Mail in an envelope addressed to: Assistant Commissioner for Patents, Washington, D.C. 20231.	
May 15, 2001 Date	<i>B. Todd Pattison</i> Signature

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RESPONSE TO OFFICE ACTION DATED FEBRUARY 5, 2001

In response to the Office Action dated February 5, 2001, having a shortened statutory period for response extended one month to June 5, 2001, please enter the following amendments and reconsider the claims pending in the application for reasons discussed below.

**IN THE CLAIMS:**

Please replace the following claims:

C1 1. (Amended) A method for processing a substrate in a processing chamber, comprising exposing a patterned substrate surface to a plasma generated from a gas mixture consisting of argon, helium and hydrogen, wherein the gas mixture comprises less than about 75% by volume of argon.

C2 3. (Amended) The method of claim 1, wherein the hydrogen is provided to the processing chamber in a mixture of about 95% by volume of helium and about 5% by volume of hydrogen.